

IN THE CLAIMS:

Please CANCEL claims 1-20 without prejudice to or disclaimer of the recited subject matter.

Please ADD new claims 21-36, as follows. For the Examiner's convenience, all claims currently pending in this application have been reproduced below:

1-20. (Canceled)

21. (New) An exposure apparatus for exposing a substrate to light via a mask, said apparatus comprising:

a projection optical system configured to project a pattern of the mask onto the substrate;

a cover configured to surround a path of light from said projection optical system toward the substrate;

a first supply port arranged inside said cover and configured to supply inert gas inside said cover;

a first recovery port arranged inside said cover and configured to recover gas inside said cover;

a second supply port arranged outside said cover and configured to supply gas outside said cover; and

a second recovery port arranged outside said cover and configured to recover gas outside said cover,

wherein a first direction from said first supply port to said first recovery port and a second direction from said second supply port to said second recovery port oppose each other at an angle not greater than 90°.

22. (New) An apparatus according to claim 21, further comprising:

a controller configured to control at least one of a first flow rate of inert gas supplied inside said cover and a second flow rate of gas recovered from inside said cover so that the first flow rate is greater than the second flow rate.

23. (New) An apparatus according to claim 22, further comprising:

a first pressure sensor configured to measure pressure inside said cover; and  
a second pressure sensor configured to measure pressure outside said cover,  
wherein said controller is configured to control at least one of the first flow rate and the second flow rate based on measurements obtained by said first and second pressure sensors.

24. (New) An apparatus according to claim 21, wherein the first direction and the second direction are opposite to each other at an angle not greater than 45°.

25. (New) An apparatus according to claim 21, wherein the first direction and the second direction are just opposite to each other.

26. (New) An apparatus according to claim 21, wherein said second supply port is configured to supply gas having an impurity concentration higher than that of inert gas supplied through said first supply port.

27. (New) An apparatus according to claim 21, further comprising:  
a third supply port arranged at a first portion of a bottom of said cover under said first supply port and configured to supply inert gas into a space between the first portion and the substrate.

28. (New) An apparatus according to claim 27, further comprising:  
a controller configured to control at least one of a first flow rate of inert gas supplied through said first and third supply ports and a second flow rate of gas recovered through said first recovery port so that the first flow rate is greater than the second flow rate.

29. (New) An apparatus according to claim 27, wherein said apparatus is a scanning exposure apparatus, and a scanning direction of the substrate and the first direction are substantially parallel to each other.

30. (New) An apparatus according to claim 29, further comprising:

a fourth supply port arranged at a second portion of a bottom of said cover under said first recovery port and configured to supply inert gas into a space between the second portion and the substrate.

31. (New) An apparatus according to claim 21, further comprising:

a third recovery port arranged at a first portion of a bottom of said cover under said first supply port and configured to recover gas from a space between the first portion and the substrate.

32. (New) An apparatus according to claim 31, further comprising:

a controller configured to control at least one of a first flow rate of inert gas supplied through said first supply port and a second flow rate of gas recovered through said first and third recovery ports so that the first flow rate is greater than the second flow rate.

33. (New) An apparatus according to claim 31, wherein said apparatus is a scanning exposure apparatus, and a scanning direction of the substrate and the first direction are substantially parallel to each other.

34. (New) An apparatus according to claim 33, further comprising:

a fourth recovery port arranged at a second portion of a bottom of said cover under said first recovery port and configured to recover gas from a space between the second portion and the substrate.

35. (New) An apparatus according to claim 21, further comprising:

a straightening member arranged at a bottom of said cover under said first supply port.

36. (New) A method of manufacturing a device, said method comprising steps of:

exposing a substrate to light using an exposure apparatus as defined in claim 21;

developing the exposed substrate; and

processing the developed substrate to manufacture the device.